

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2004-018593
(43)Date of publication of application : 22.01.2004

(51)Int.Cl.

C08G 73/22
C08J 5/18
G03F 7/004
G03F 7/037
H01B 3/30
H01L 21/027
H01L 21/312
H01L 21/768
// C08L 79:04

(21)Application number : 2002-172884

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(22)Date of filing : 13.06.2002

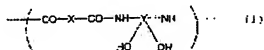
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(54) POLYBENZOXAZOLE PRECURSOR, PHOTSENSITIVE RESIN COMPOSITION AND ELECTRONIC PART

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a polybenzoxazole precursor whose i-line transmission is good and can form the polybenzoxazole having a low relative dielectric constant and high thermal resistance, to provide a photosensitive resin composition using the same, and to provide an electronic part using the same.

SOLUTION: This polybenzoxazole precursor has repeating units represented by the general formula (1) (X is a divalent organic group; Y is a tetravalent organic group; two or one of X and Y have adamantane structures in the main chains). The photosensitive resin composition and the electronic part each uses the polybenzoxazole precursor.



LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's]

decision of rejection]

[Date of extinction of right]

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